

DEPARTMENT OF MATERIAL SCINCE AND ENGINEERING NITC CALICUT



JOB REQUISITION FORM FOR MULTISOURCE PHYSICAL VAPOUR DEPOSITIONSYSTEM

Name:	Designation:			
Address:	Contact number:			
(Institution/Department)				
	Email ID:			
Supervisor:	Contact number:			
	Email ID:			
Internal (NITC)/External/Industry				
Number of depositions				
Is Co-deposition required? (tick any one) : YES/NO				

Technical Details:

DC / RF power required	
Sputtering Distance / Time	
Substrate Cleaning	Required/ Not Required
Gas flow rate (Ar)	

PVD Source	Description of Material to be deposited	Description of Substrate material	Desired film thickness (Limited to	Co-sputtering/Co- evaporation required, if yes mention the differentmaterials
			200- 300 nm)	
Thermal				
Evaporation				
RF				
Magnetron Sputtering				
Sputtering				
DC Magnetron Sputtering				



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This work is part of the research activity of the department / center. No remuneration or compensation is received from any agency. Further, it is certified that the sample(s) do not pose ahealth risk to anybody.

Date:		Signature of Researcher						
Recommendation of Supervi	:							
Signature of the Head of the	Dept/Institution	n :	:					
	For lab	oratory use:						
Job priority: high/medium/low								
Ref no:		Date and time allotted:						
Job completed on		Remarks:						
date:		Kellai KS.						
Signature of faculty in-charge								
Approval Director,				ector,				
For office use								
Ref. No:	Date:							
Name and institution of the user								
Deposition (Technique)								
Deposition charges								
Payment details	DD/Cheque no.	Date	Bank name	Amount				
Name of the faculty who conducted the experiment			•	,				